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(12) **United States Design Patent**  
**Kuwabara et al.**

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(54) **ELECTRODE PLATE FOR A PLASMA  
PROCESSING APPARATUS**

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(73) Assignee: **Tokyo Electron Limited**, Tokyo (JP)

(\*\*) Term: **14 Years**

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(51) **LOC (10) Cl.** ..... **13-03**

(52) **U.S. Cl.**  
USPC ..... **D13/182**

(58) **Field of Classification Search**  
USPC ..... D13/182; D15/144, 144.1, 199;  
118/715; 414/935-941, 147, 217;  
156/345.53; 279/128; 361/230, 233,  
361/234; 204/193, 194, 279, 280, 281, 282,  
204/283, 284, 285, 286.1, 297.01; 205/118,  
205/123; 200/293, 302.1, 308

See application file for complete search history.

(56) **References Cited**

**U.S. PATENT DOCUMENTS**

D363,464 S \* 10/1995 Fukasawa ..... D13/182  
D404,370 S \* 1/1999 Kimura ..... D13/182  
D404,372 S \* 1/1999 Ishii ..... D13/182  
D411,516 S 6/1999 Imafuku et al.  
6,818,097 B2 \* 11/2004 Yamaguchi et al. .... 156/345.47  
D546,784 S \* 7/2007 Hayashi ..... D13/182  
D548,705 S \* 8/2007 Hayashi ..... D13/182  
D556,704 S \* 12/2007 Nakamura et al. .... D13/182  
D557,226 S \* 12/2007 Uchino et al. .... D13/182  
7,479,304 B2 \* 1/2009 Sun et al. .... 427/289  
D606,952 S \* 12/2009 Lee et al. .... D13/182

D609,652 S \* 2/2010 Nagasaka et al. .... D13/182  
D609,655 S \* 2/2010 Sugimoto ..... D13/182  
D614,593 S \* 4/2010 Lee et al. .... D13/182  
D648,289 S \* 11/2011 Mayer et al. .... D13/182  
D654,883 S \* 2/2012 Honma et al. .... D13/182

(Continued)

**FOREIGN PATENT DOCUMENTS**

KR 30-0335385 10/2003

**OTHER PUBLICATIONS**

Taiwanese Office Action, Application No. 101301746, dated Oct. 24, 2012.

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(57) **CLAIM**

The ornamental design for an electrode plate for a plasma processing apparatus, as shown and described.

**DESCRIPTION**

FIG. 1 is a front view of an electrode plate for a plasma processing apparatus showing our new design, the rear view being identical;

FIG. 2 is a right side view thereof, the left side view being identical;

FIG. 3 is a top plan view thereof;

FIG. 4 is a bottom plan view thereof;

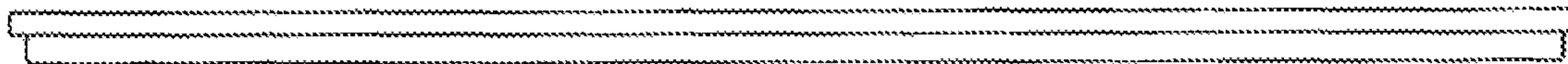
FIG. 5 is an enlarged view of a portion of the electrode plate for a plasma processing apparatus of FIG. 1 taken along line 1-1 and line 2-2 of FIG. 3;

FIG. 6 is an enlarged cross sectional view thereof, taken along line 3-3 of FIG. 5; and,

FIG. 7 is a perspective view of the electrode plate for a plasma processing apparatus of FIG. 1.

The features shown only in broken lines depict environmental subject matter only and form no part of the claimed design.

**1 Claim, 7 Drawing Sheets**



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(56)

## References Cited

### U.S. PATENT DOCUMENTS

D655,257 S *	3/2012	Honma et al. ....	D13/182	
D655,259 S *	3/2012	Honma et al. ....	D13/182	
2003/0066484 A1 *	4/2003	Morikage et al. ....	118/723 E	
D654,884 S *	2/2012	Honma et al. ....	D13/182	* cited by examiner

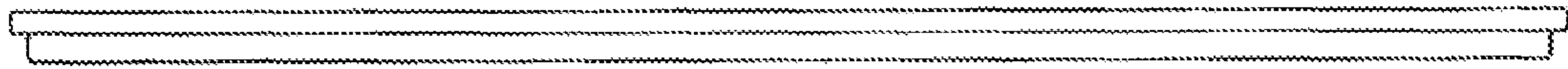


Figure 1

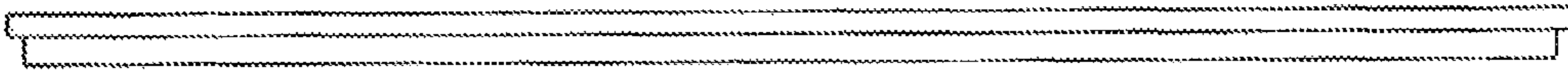


Figure 2

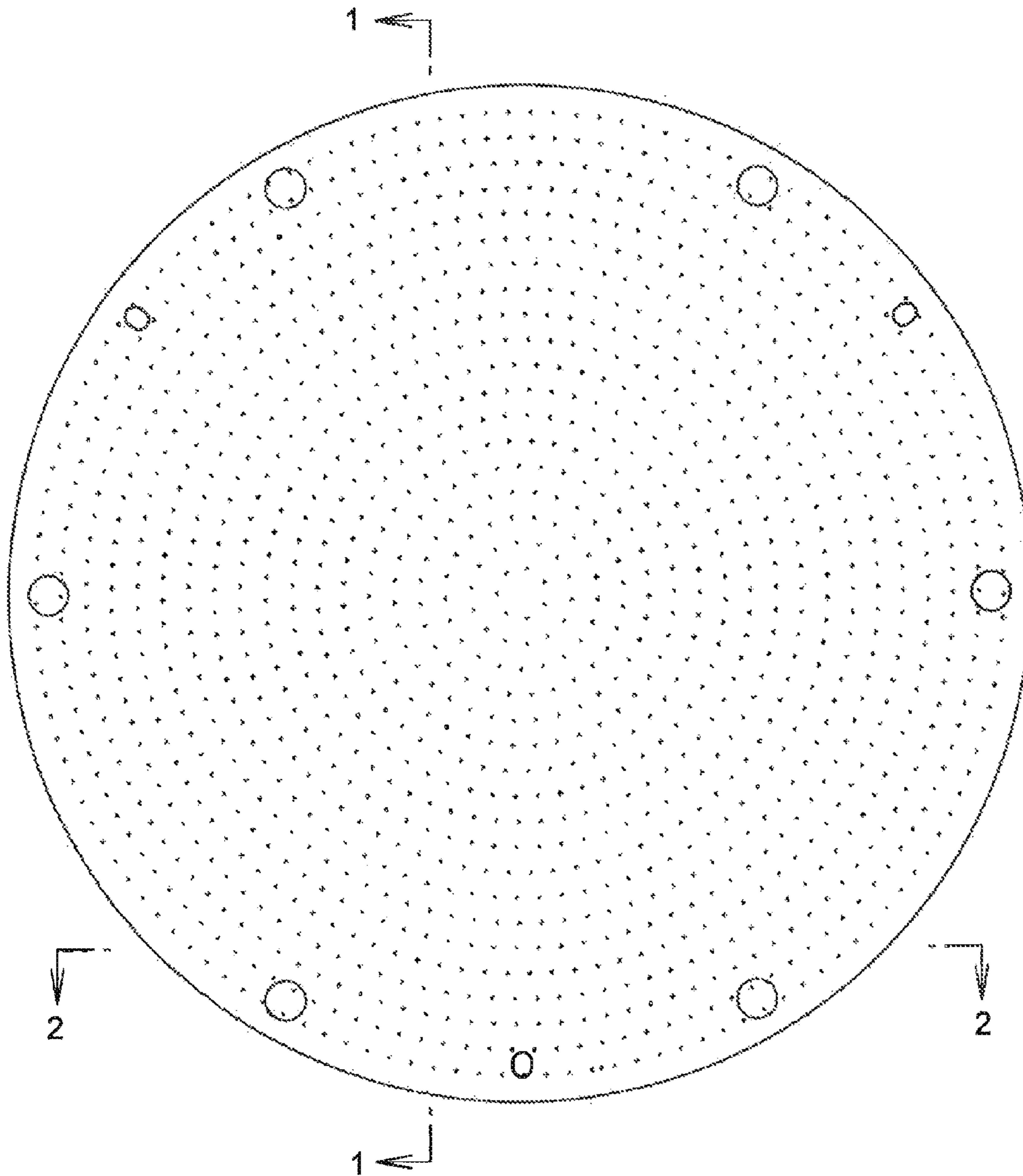


Figure 3

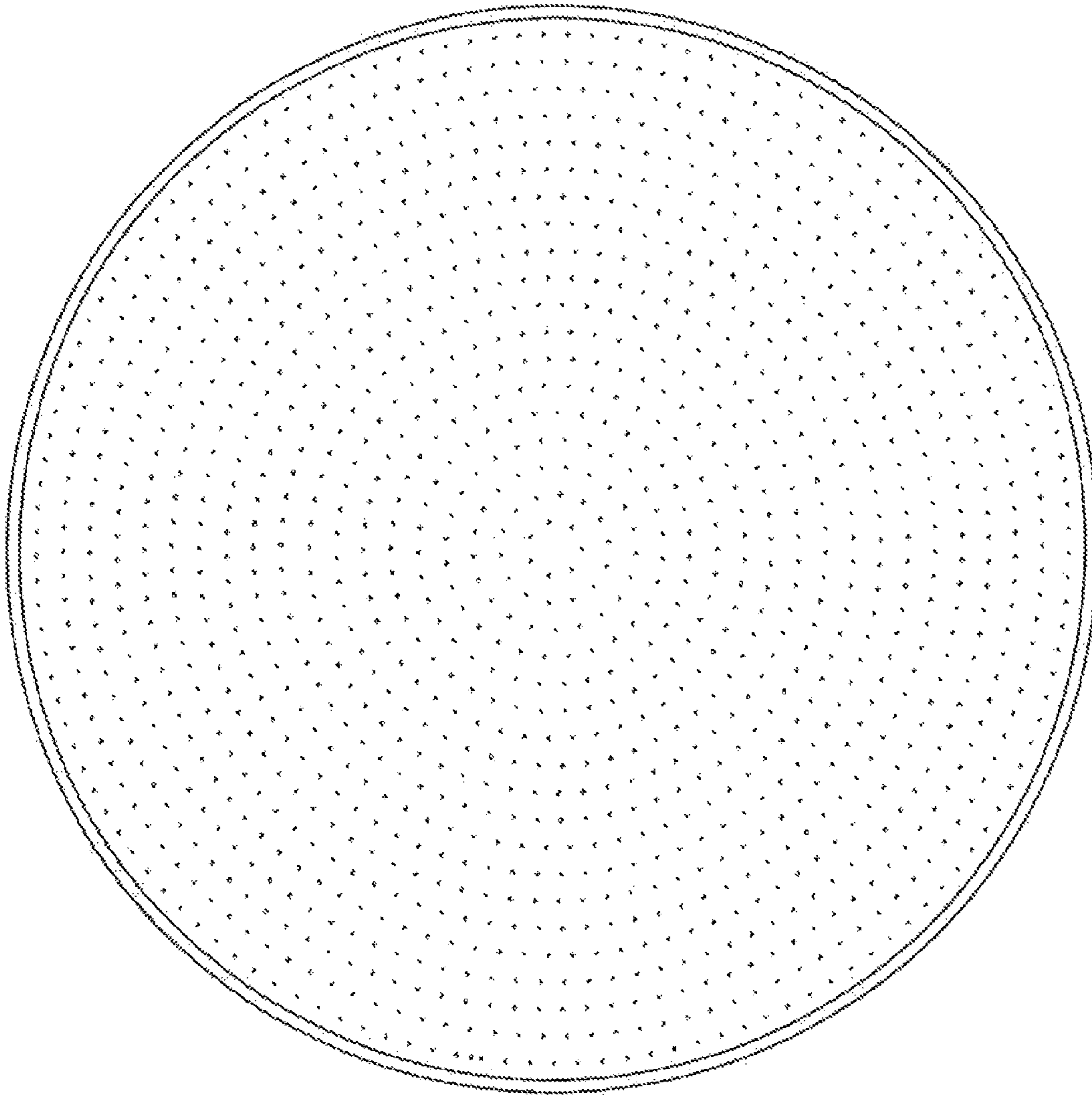


Figure 4

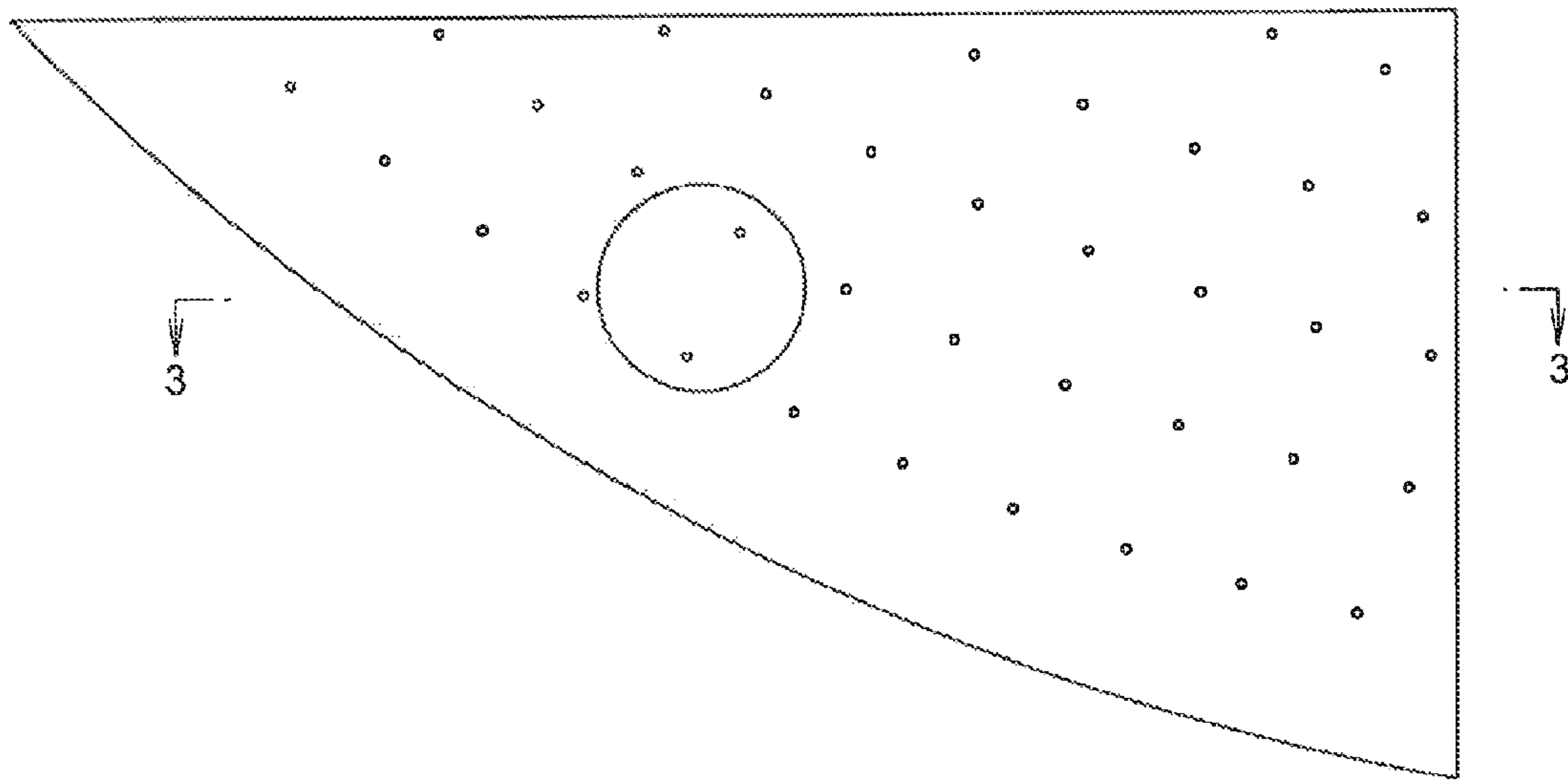


Figure 5

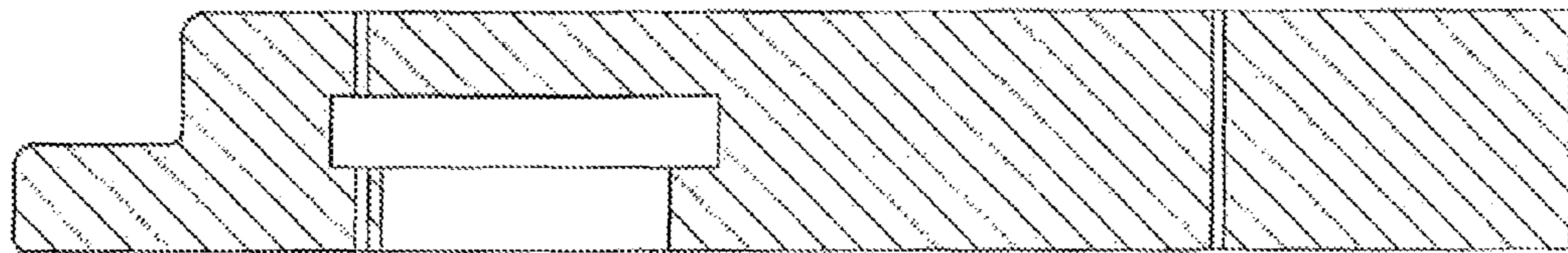


Figure 6



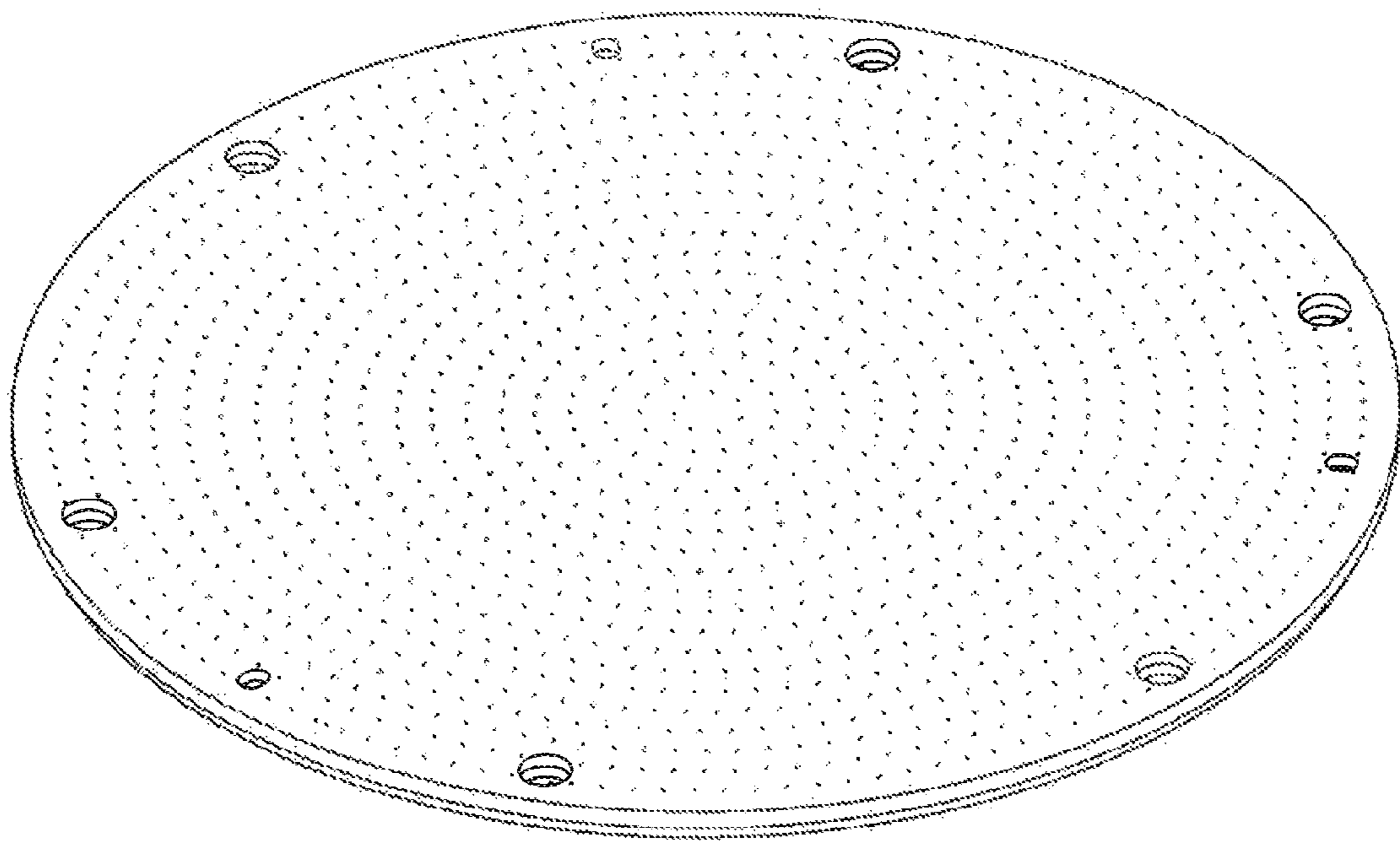


Figure 7